

49 48708

~~2~~ Active

211

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L2: (6571) 1 and (organic or polymer).clm.
L3: (2133) 2 and (electrode.clm.)
L4: (1507) 3 and ((second or top or upper) near
L5: (1224) 4 and (etch$3 or pattern$3)
L6: (451) 5 and ((etch43 or pattern$3) near7
L7: (189) 6 and (organic adj1 layer)
L8: (360) 6 and (organic adj3 layer)
L9: (234) 8 and ((etch$3 or pattern$3) adj4 o
L10: (38) 9 and ((etch$3 or pattern$3) adj4 o
L11: (33) 10 and (mask or resist or photoresi
L12: (18) 11 and (mask or resist or photoresi
L13: (409) 6 and (organic adj3 (film or layer:
L14: (102) 13 and (mask or resist or photores
L15: (66) 14 and (silicon$6)
L16: (61) 15 and (electrode with organic)
L17: (59) 16 and (electrode near9 organic)
L18: (33) 17 and (organic adj2 (memory or dev
L19: (4) 17 and (silicon near4 (resist or pho

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Age	Sex	Subject	Grade	Class
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DATE: 10/24/2005

100

Figure 1

[illegible]

17 and (silicon nitride (resist or photoresist or photomask or mask))

 USB drive
 Floppy disk
 Printer
 Network
 Power

[illegible]

WEST - [resistor.wsp.1]

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- L1: (2) (("6746899") or ("6737704")).PN.
- L2: (4) (("6,278,148") or ("6,218,631") or ("5,610,403") or ("5,
- L3: (6) "6458674".
- L4: (1) ("6458674").PN.
- L5: (10) (("6324091") or ("6320200") or ("6348700") or ("4663270
- L6: (7) 5 and organic
- L7: (7) 5 and (organic or polymer)
- L8: (0) 7 and (silicon\$5 with (resist or mask or photoresist))
- L9: (2) 7 and (resist or mask or photoresist)
- L10: (160890) electrode.clm.
- L11: (14192) 10 and (organic or polymer).clm.
- L12: (1241) 11 and (resist or photoresist or mask).clm.
- L13: (983) 12 and (pattern\$3 or etch\$3).clm.
- L14: (408) 13 and ((resist or photoresist or mask) with (silicon
- L15: (201) 14 and ((organic or polymer) with electrode)
- L16: (199) 15 and ((etch\$3 or pattern\$3) with (electrode or orga
- L17: (199) 15 and ((etch\$3 or pattern\$3) same (electrode or orga
- L18: (62) 17 and (memory or ((second or top or upper) adj electr
- L19: (62) 18 and (resist or mask or photoresist).clm.
- L20: (62) 19 and (etch\$3 or pattern\$3).clm.
- L21: (62) 20 and ((etch\$3 or pattern\$3) near10 (resist or mask o
- L22: (60) 20 and ((etch\$3 or pattern\$3) near10 (organic or polym
- L23: (59) 22 and ((etch\$3 or pattern\$3) near5 (organic or polyme
- L24: (29) 23 and polymer
- L25: (7) 12 and (polysiloxane or silsesquioxane)
- L26: (1) 11 and ((resist or photoresist or mask) with (polysilox
- L27: (463) 12 and ((resist or mask or photoresist) near8 (silico
- L28: (178) 27 and (organic with electrode)
- L29: (178) 28 and (organic or polymer).clm.
- L30: (129) 29 and ((organic or polymer) near8 electrode)
- L31: (40) 30 and ((top or second or upper) adj electrode)
- L32: (16) 31 and dielectric
- L33: (37) 31 and ((top or second or upper) adj electrode).clm.
- L34: (32) 33 and (etch\$3 or pattern\$3).clm.
- L35: (32) 34 and (resist or mask or photoresist).clm.

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34 and (resist or mask or photoresist).clm.

U	I	P	T	P	Document ID	Issue Dat	Pages	Title	Current OF	Current XN	Retrieval	Inventor	S	C	J	A	S
					US	20040415	50	Light emitting device	438/30			Yamazaki, Shunpei					
					20040072380			and method for manufact				et al.					
					US	20040325	30	Method for etching	438/710			Higuchi, Kenichi					

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